

35th EUROPEAN SYMPOSIUM

on Reliability of Electron
Devices, Failure
Physics and Analysis



PROCEEDINGS

September 23-26, 2024

PARMA, Italy

www.esref2024.org

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WELCOME TO ESREF 2024

Dear colleagues,

on behalf of the Scientific and Organizing committees, we are pleased to welcome you to ESREF 2024, the 35th European Symposium on Reliability of Electron Devices, Failure Physics and Analysis. This year the conference takes place in Parma, Italy, from September 23 to 26, 2024. This International Symposium continues its 35-year history of focusing on the latest research developments and future directions in failure analysis, quality, and reliability of materials, devices, and circuits for microelectronics and optoelectronics, power, space, and automotive electronics. ESREF historically provides a European forum to develop all reliability aspects, including management and advanced failure analysis techniques for present and emerging semiconductor applications.

This edition is a special one: in 2024, ESREF will celebrate its return to Italy after 12 years. The Conference is held in the Motor Valley, a very productive region with many automotive brands and great know-how on the latest automotive technologies.

Besides, ESREF 2024 is a unique opportunity to get in contact with Italian universities, with their unequalled background in the reliability of automotive and electronic systems for automation.

Electronics enhance our safety and comfort, playing a crucial role in helping us understand and shape the world we live in. As we confront the challenges before us, we are confident that electronics can and should be integral to the solutions. Reliability is fundamental to improving sustainability, sovereignty, security, and safety.

This year's ESREF Conference has once again attracted exceptional contributions from across the globe. The presentations have been organized in 16 oral sessions and two days of interactive poster sessions, covering Quality and Reliability Assessment Techniques, Semiconductor Failure Mechanisms, Progress in Failure Analysis, Reliability of Microwave Devices, Packaging- and Assembly Reliability, Power Device Reliability, Photonics Reliability, MEMS and Sensors Reliability, Extreme Environments and Radiation. This year, a new track on Automotive and Industrial Electronic Reliability has also been added, to meet the new challenges related to the development of sustainable mobility and smart industry.

On the first day, two tutorials of great interest will open the conference, by discussing timely and relevant topics:

- **GAUDENZIO MENEGHESSO**, University of Padova, Italy, GaN reliability: from technological considerations to failure processes
- **HUAI WANG**, Aalborg University, Denmark, AI-assisted reliability testing, modeling, and condition monitoring for power electronics applications

The program will be enriched by the contribution of four distinguished experts, who joined the conferences as keynote speakers.

Semiconductor Keynotes:

- **HARALD GOSSNER**, Intel Senior Principal Engineer, IEEE Fellow, Intel CCG a Group, Munich, Germany
- **GIANLUCA BOSELLI**, ESD Team Manager and Director of Advanced Technology Development University Research Program, Advanced Technology Development, Texas Instruments, Dallas, Texas, USA

Automotive Keynotes:

- **GIORGIO GULLONE**, Simulation and Control Specialist at Ferrari S.p.A., Italy
- **LUCA ZACHEO**, Benches & Automations Management at Automobili Lamborghini S.p.A., Italy

Moreover, six invited talks will guide the audience into the latest developments in microelectronics and reliability.

In the tradition of the conference, we will also welcome, as invited, speakers who have received best paper awards at our sister conferences IPFA, and ISTFA.

Finally, the conference program includes three workshops on important topics in electronics reliability, which will be discussed by experts from industry and academia:

- **Automotive Electronic Workshop - Driving into the future**
- **Reliability of WBG Power Conversion**
- **Hardware Security Meets Failure Analysis**

This conference has been made possible through the generous contributions of our sponsors, exhibitors, and industrial partners. We extend our gratitude to them. Their belief in our conference and support for the development and execution of our exceptional technical and social program have been invaluable.

Lastly, we would like to extend our heartfelt thanks to the track chairs and to all the reviewers and members of the Scientific Committee, who generously volunteered their time and expertise to review the papers. Their efforts have been instrumental in ensuring that this conference meets the high technical and professional standards we strive for.

We hope all of you will enjoy the conference, the scientific interaction, and the lively discussions!



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B - Semiconductor Failure Mechanisms and Reliability for Si Technologies & Nanoelectronics

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C - Progress in Failure Analysis: Defect Detection and Analysis

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D - Reliability of Microwave Devices and Circuits

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E - Packaging and Assembly Reliability and Failure Analysis

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F1 - Power Devices Reliability: Smart-Power Devices and Silicon Power Devices

GIOVANNI BREGLIO University of Napoli (IT)

ZOUBIR KHATIR Gustave Eiffel University (FR)

F2 - Power Devices Reliability: Wide Bandgap Devices

FARID MEDJDOUB CNRS-IEMN (FR)

MATTEO MENEGHINI University of Padova (IT)

F3 - Power Devices Reliability: Power Electronic Systems

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G - Photonics Reliability

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H - MEMS and Sensors Reliability

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L- Automotive and Industrial Electronic Reliability

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CONFERENCE PROGRAM

Monday, September 23rd

09:00 Tutorials

CHAIR: *Nicola Delmonte*
University of Parma, Italy

09:00 AI-assisted reliability testing, modeling, and condition monitoring for power electronics applications

[Huai Wang](#)
Aalborg University, Denmark

11:00 GaN reliability: from technological considerations to failure processes

[Gaudenzio Meneghesso](#)
University of Padua, Italy

14:00 Opening session

CHAIR: *Paolo Cova*
University of Parma, Italy

14:40 Session K1: Semiconductors Keynotes

CHAIR: *Francesco Iannuzzo*
Aalborg University, Denmark

14:40 The Reliability Perspective of the Advanced CMOS Roadmap

[Harald Gossner](#)
Intel, Germany

15:20 System-Level ESD Design in HV Automotive Applications: Process, IP and System Co-Design Challenges

[Gianluca Boselli](#)
Texas Instruments, United States

16:20 Session F1: Power devices reliability: smart-power devices and silicon power

CHAIRS: *Giovanni Breglio*¹ *Zoubir Khatir*²
¹University of Naples Federico II, Italy ²Gustave Eiffel University, France

16:20 **(Invited)** Out-of-SOA Electrothermal Limitations of Power Semiconductor Devices: Characterization and Modeling

[Andrea Irace](#)¹
¹University of Napoli "Federico II", Italy

17:00 [New Temperature-Independent Aging Indicator for power semiconductor devices – application to IGBTs](#)

[Zoubir Khatir](#)¹, [Ali Ibrahim](#)¹ [Richard Lallemand](#)¹
¹University Gustave Eiffel, France

17:20 [Effect of load sequence interaction for low \$\Delta T_j\$'s on the reliability of bonded aluminium wires in IGBTs](#)

[Ayda Halouani](#)¹, [Zoubir Khatir](#)¹, [Richard Lallemand](#)¹, [Ali Ibrahim](#)¹ [Damien Ingrassio](#)¹
[Nicolas Degrenne](#)²

¹University Gustave Eiffel, France; ²Mitsubishi Electric R&D Centre Europe, France

17:40 [Improvement of Sensitivity for Power Cycle Degradation by A New Device Structure](#)

[Koki Okame](#)¹, [Yuki Yamakita](#)¹, [Shin-Ichi Nishizawa](#)², [Wataru Saito](#)²
¹Interdisciplinary Graduate School of Engineering Science, Japan; ² Kyushu University, Japan

18:00 [Impact of IGBT emitter pad design and front- side ageing on switching stability](#)

[Christian Bäuml](#)¹, [Thomas Basler](#)¹
¹Chemnitz University of Technology, Germany

17:00 Session B: Silicon technologies, nanoelectronics and MEMS: from device reliability to back-end reliability

CHAIRS: *Alain Bravaix*¹, *George Papaioannou*²
¹ISEN, France, ²University of Athens, Greece

17:00 [Reading reliability in 1S1R OTS+PCM devices based on Double Patterned Self Aligned structure](#)

[Renzo Antonelli](#), [Guillaume Bourgeois](#), [Valentina Meli](#), [Zineb Saghi](#), [Théo Monniez](#), [Simon Martin](#),
[Niccolò Castellani](#), [Mathieu Bernard](#), [Leïla Fellouh](#), [Antoine Salvi](#), [Sylvain Gout](#), [François Andrieu](#),
[Abdelkader Souifi](#), [Gabriele Navarro](#)
Univ. Grenoble Alpes, France

- 17:20 [Electrical and reliability characterization with optimized extrapolation models of two- and three-dimensional Metal-Insulator-Metal decoupling capacitors with ZrAlxOy high-k dielectric under BEOL-friendly conditions](#)
Konstantinos Efstathios Falidas¹, Kati Kühnel¹, Matthias Rudolph¹, André Reck¹, Malte Czernohorsky¹, Johannes Heitmann²
¹Fraunhofer IPMS, Germany, ²Technische Universität Bergakademie Freiberg, Germany
- 17:40 [Vertically Scaled Cu/low-k Interconnect Development for BEOL Reliability Improvement of 12nm DRAM](#)
Jaehyeong Lee, Byoungwook Woo, Yumi Lee, Namhyun Lee, Young-Yun Lee, Yunsung Lee, Seungbum Ko, Sangwoo Pae
 Samsung Electronics, South Korea
- 18:00 [Evaluation of the Impact of Body Bias on the Threshold Voltage Drift of SiO2 Transistors](#)
Konstantinos Tselios¹, Theresia Knobloch¹, Dominic Waldhoer¹, Hubert Enichlmair², Eleftherios G. Ioannidis², Rainer Minixhofer², Tibor Grasser¹, Michael Waltl¹
¹TU Wien, Austria, ²ams-OSRAM AG, Austria
- 18:20 [On the electrical properties of ALD HfO2 dielectric films for MEMS capacitive switches.](#)
John Theocharis¹, Paolo Martins², Aymen Mahjoub², Etienne Eustache², Afshin Ziaei², George Papaioannou¹
¹University of Athens, Greece, ²Thales Research and Technology, France

Tuesday, September 24th

08:20 Session K2: Automotive Keynotes

CHAIR: *Nicola Delmonte*
 University of Parma, Italy

08:20 Battery Diagnostics and Virtual Sensors in Ferrari

Giorgio Gullone
 Ferrari S.p.A., Italy

09:00 An approach to Electronic Platform Complexity: the System Integration in Lamborghini

Luca Zacheo
 Lamborghini S.p.A., Italy

10:00 Session A-1: Accelerated life tests and design of experiments

CHAIR *Edgar Olthof*
 NXP Semiconductors, Netherlands

10:00 [Design-of-Experiments and ALT plan for reliability qualification of chip resistors based on mission profile of AIMDs](#)

Fatima-Ezahra Indmeskine¹, Laurent Saintis¹, Abdessamad Kobi¹, H el ene Marceau²
¹University of Angers, France, ²TAME-COMPONENT (TRONICO), France

10:20 [Reliability Assurance in Foldable Displays: Design of Experiment-Based Testing Strategy for Market-Ready Products](#)

Ui Hyo Jeong¹, Seongyong Lim², Seung Su Han¹
¹Korea Testing Certification, South Korea, ²Incheon National University, South Korea

10:40 [New statistical analysis methodology to forecast the memory cell behavior before reliability test](#)

Sebastien Perrin¹, Vincenzo Della Marca², Thibault Kempf¹, Marc Bocquet², Loic Welter¹, Jean-Michel Moragues¹, Arnaud Regnier¹, Jean-Michel Portal²
¹STMicroelectronics, France, ²Aix-Marseille University, France

11:00 [Condition Monitoring for Detection of Humidity-Induced Failures in Control Electronics of Power Converters](#)

Frederic Sehr¹, Stefan Wagner¹, Adelja Schulz¹, Alexander Vorwerk¹
¹Fraunhofer Institute for Reliability and Microintegration (IZM), Berlin, Germany

10:00 Session L: Automotive and industrial electronic reliability

CHAIRS: *Nicola Trivellin¹, Ulrich Abelein², Michael Nelhiesel³*
¹University of Padova, Italy, ²Infineon Technologies AG, Germany, ³KAI Kompetenzzentrum Automobil- und Industrieelektronik GmbH, Austria

10:00 [Reliability analysis of high power LEDs for automotive: impact of current and temperature](#)

Alessandro Caria, Nicola Trivellin, Riccardo Fraccaroli, Nicola Roccatto, Matteo Buffolo, Carlo De Santi, Gaudenzio Meneghesso, Enrico Zanoni, Matteo Meneghini
 University of Padova, Italy

10:20 [Aging modelling of Li-Ion Battery Systems based on accelerated tests](#)

Andrea Toscani, Mattia Stighezza, Marco Simonazzi, Nicola Delmonte, Paolo Cova, Valentina Bianchi, Ilaria De Munari
 University of Parma, Italy

10:40 [Development challenges of a one-sided GaN- based high-current density buck converter through multiphysics optimization for electric vehicle applications](#)

Mohamed Belquith¹, Sonia Eloued², Moncef Kadi³, Jaleddine Ben Hadj Slama²

¹Université de Sousse, Tunisia / Université Rouen Normandie, France, ²Université de Sousse, Tunisia, ³Université Rouen Normandie, France

11:00 [Performance characterization of lithium-ion battery and ageing under constant stress conditions at low temperature](#)

Ossama Rafik, Armande Capitaine, Olivier Briat, Jean-Michel Vinassa

IMS Bordeaux, France

11:20 [SMART Protection Design of Automotive Power Distribution Systems with Temperature-Based Electronic Fuses: Mathematical Background, Design Guidelines and Drawbacks of Energy-Based Methods](#)

Mirko Bernardoni, Robert Illing, Mario Tripolt, Christian Djelassi-Tscheck

Infineon Technologies Austria, Austria

12:00-14:00 Poster Session 1

CHAIR: *Giovanna Mura*

University of Cagliari, Italy

[Degradation model for insulation characteristics of tantalum capacitors related to manufacturing parameters and stress](#)

Xue Zhou, Mingxu Zhang, Donghui Li, Chensong Ji, Le Xu, Guofu Zhai

Harbin Institute of Technology, China

[Research on The Degradation of Contact Resistance of Wire-Spring Contacts in Different Wear Condition](#)

Le Xu, Yuyao Zhao, Shujuan Wang

Harbin Institute of Technology, China

[Reliability Design of GaN Based High-frequency Inverter Optimization](#)

Ya Jing Zhang¹, Xin Yu Ao¹, Hong Li¹, Xiu Teng Wang²

¹Beijing Information Science and Technology University, China, ²China National Institute of Standardization, China

[Correlating time and voltage laws in BTI](#)

Joseph Bernstein¹, Alain Bensoussan², Emmanuel Bender³, Tsuriel Abraham¹

¹Ariel University, Israel, ²ReEEs Reliability, France, ³MIT, Israel

[Evidence of resistive switching in SiNx thin films for MEMS capacitors: the role of metal contacts](#)

John Theocharis, Spiros Gardelis, George Papaioannou

National and Kapodistrian University of Athens, Greece

[Recovery and Unrecovered Damage During Interrupted CVS in MFIS FE devices](#)

Tiang Teck Tan¹, Tian-Li Wu², Kalya Shubhakar¹, Nagarajan Raghavan¹, Kin Leong Pey¹

¹Singapore University of Technology and Design, Singapore, ²National Yang Ming Chiao Tung University, Taiwan

[HTRB effects on threshold instability of 4H-SiC PowerMOSFET with carrots defects](#)

Laura Anoldo¹, Giuseppe Tosto¹, Santina Bevilacqua¹, Erwin Schroer¹, Salvatore Patanè², Alfio Russo¹

¹STMicroelectronics, Italy, ²University of Messina, Italy

[Thermal layout optimization of electrolytic capacitors considering degradation self- acceleration effect for reliability improvement](#)

Xuerong Ye¹, Qisen Sun², Ruyue Zhang³, Junpeng Gao¹, Haodong Wang¹, Guofu Zhai¹

¹Harbin Institute of Technology, China, ²City University of Hong Kong, Hong Kong, ³China Jiliang University

[Semi-supervised parameter estimation for Synthetic Aperture Focusing in Scanning Acoustic Microscopy for a 3D reconstruction of plastic molded electronic devices](#)

Mario Wolf¹, Peter Hoffrogge², Michael Wiedenmann³, Stefan Oberhoff³, Christian Kupsch¹, Jörg Krinke³, Peter Czurratis²

¹TU Bergakademie Freiberg, MSE Lab, Germany, ²PVA TePla Analytical Systems GmbH, Germany, ³Robert Bosch GmbH, Germany

[Reliability detection and analysis of elliptical holes corresponding to defects in electrothermal environment](#)

He Zhang, Li Wang, Jiwen Cui

Harbin Institute of Technology, China

[On the influence of the porosity and homogeneity of sintered die-attach layers on the power cycling performance](#)

Lukas Mikutta, Frederik Otto, Jörg Schadewald

Infineon Technologies AG, Germany

[Aging impact of the SiC Mosfet gate dielectric](#)

Tanguy Phulpin, Alexandre Jaffré, Pascal Chrétien, David Alamarguy

GeePs, France

[Failure mode competition and long-term reliability in the isothermal aging of sintered Cu joints](#)

Jianbo Xin¹, Xiaochun Lv², Yue Gao³, Le Yang¹, Sushi Liu¹, Ke Li¹, Minghao Zhou¹, William Cai¹, Jing Zhang³, Yang Liu¹

¹Harbin Institute of Technology, China, ²Harbin Welding Institute Limited Company, China, ³Heraeus Electronic Technology, Shanghai, China

[Investigating the thermal degradation trends for thermal interface materials in the power converter](#)

Ziheng Wang¹, Yi Zhang¹, Huai Wang¹

¹Aalborg University, Denmark

[PBO Delamination and RDL Corrosion detection on WLCSP Package Products](#)

Klodjan Bidaj¹, Yong Chen², Jason Chang³, Orianne Atance-Loustaunau³, Francois Braud¹

¹STMicroelectronics, France, ²STMicroelectronics, Singapore, ³STMicroelectronics, Taiwan

[Laser voltage probing and simulation of a flip-flop with undesired quasi-static switching](#)

Angelo Antonio Merassi¹, Tommaso Melis²

¹STMicroelectronics, Italy, ²STMicroelectronics, France

[Multi-sensor Data Fusion for Prediction of Remaining Useful Life of IGBT Power Modules](#)

Martin Votava¹, Karthik Debbadi¹, Gopal Mondal², Sebastian Nielebock², Yoann Pascal¹, Marco Liserre¹

¹Fraunhofer Institute for Silicon Technology ISIT, Germany, ²Siemens AG, Germany

[Effect of Drain Field Plate design and 2DEG density on Dynamic-ROn of 650V AlGaIn/GaN HEMTs](#)

Marcello Cioni¹, Giovanni Giorgino¹, Alessandro Chini², Nicolo Zagni², Giacomo Cappellini¹, Santo Principato¹, Cristina Miccoli¹, Tariq Wakrim³, Maria Eloisa Castagna¹, Aurore Constant³, Ferdinando Iucolano¹

¹STMicroelectronics, Italy, ²University of Modena and Reggio Emilia, Italy, ³STMicroelectronics, France

[Evolution analysis of mechanical behavior of through-silicon via under thermal cycling load](#)

Kaihong Hou, Zhengwei Fan, Xun Chen, Shufeng Zhang, Yashun Wang, Yu Jiang

National University of Defense Technology, Changsha, China, China

[Long-Term Positive and Negative Gate Bias Stress Tests on Parallel Connected SiC MOSFETs at -40°C and 175°C](#)

Arkadeep Deb¹, Mohamed Taha Elsayed Abdelkader¹, Jose Ortiz Gonzalez¹, Phil Mawby¹, Saeed Jahdi², Olayiwola Alatise¹

¹University of Warwick, UK, ²University of Bristol, UK

[Single Event Irradiation Damage Effect of SiC MOSFETs Based on Degradation of Forward Conduction Characteristic](#)

Pengwei Li^{1,2}, Liang Zhen², Xingji Li², Jianqun Yang², Hongwei Zhang¹, Yi Sun¹, Qianyuan Wang¹, Qingkui Yu¹, Xuhui Wang³, Guohe Zhang³

¹China Academy of Space Technology, China, ²Harbin Institute of Technology, China, ³Xi'an Jiaotong University, Xi'an, China

[Stress comparison of several short-circuit types on SiC MOSFET packaging](#)

Bin Yu¹, Xingjian Shi², Hongyi Gao², Haoze Luo², Wenbo Wang³, Francesco Iannuzzo⁴, Wuhua Li²

¹Nanjing University of Information Science and Technology/Zhejiang University, China, ²Zhejiang University, China, ³Harbin Institute of Technology, China, ⁴Aalborg University, Denmark

[The Drift in Threshold Voltage and On-Resistance of SiC MOSFETs Induced by AC Bias Temperature Instability](#)

Zicheng Wang, Cen Chen, Boya Zhang, Yifan Hu, Hao Chen, Xuerong Ye, Yaokang Lai

Harbin Institute of Technology, China

[The failure of CW high-power optical elements due to laser beams characteristics](#)

Xinyu Luo, Peng Yang, Qian Li, Jing Qiu, Guanjun Liu

National University of Defense Technology, China

[Low-Voltage Schottky p-GaN HEMT Properties under Extreme Repetitive Short-Circuit Operation Conditions : 2DEG Pinch-off, Stability, Aging, Robustness and Failure-Modes Analysis](#)

Frédéric Richardeau, Lucien Ghizzo, David Tremouilles, Sébastien Vinnac

CNRS, Toulouse, France

[Preliminary SiC MOSFET Gate-Cracking Modeling under Short-Circuit Based on Rankine's Damage Energetic Approach Using a Wide Temperature- Range Elastoplastic 2D Simulation](#)

Mustafa Shqair, Emmanuel Sarraute, Frédéric Richardeau

University of Toulouse, France

[Impact of drain-source leakage on the dynamic Ron of power HEMTs with p-GaN gate](#)

Simone Longato¹, Davide Favero¹, Arno Stockman², Arianna Nardo², Piet Vanmeerbeek², Marnix Tack², Gaudenzio Meneghesso¹, Enrico Zanoni¹, Carlo De Santi¹, Matteo Meneghini¹

¹University of Padova, Italy, ²BelGaN, Oudenaarde, Belgium

[Effect of gate oxide thickness on gate latent damage induced by heavy ion in SiC power MOSFETs](#)

Shiwei Zhao¹, Yuzhu Liu¹, Xiaoyu Yan¹, Peipei Hu¹, Xinyu Li¹, Qiyu Chen¹, Pengfei Zhai¹, Teng Zhang², Li Cai¹, Yang Jiao¹, Youmei Sun¹, Jie Liu¹

¹Institute of Modern Physics, Chinese Academy of Sciences, China, ²Nanjing Electronic Devices Institute, China, ³Nandun, Oudenaarde, Belgium

[Physics informed Markov chains for remaining useful life prediction of wire bonds in power electronic modules](#)

Mehdi Ghrabli¹, Mounira Bouarroud², Ludovic Chamoin¹, Emanuel Aldea¹

¹Université Paris Saclay, France, ²Créteil University, Paris, France

[Remaining Useful Life Prediction of DC Contactor Based on LSTM](#)

Yu Wang¹, Yong Xie², Huimin Liang¹, Hangyu Ma¹

¹Harbin Institute of Technology, China, ²GA Technologies Co.Ltd., China

[Investigation of the long-term dynamic Rds\(ON\) variation and dynamic high temperature operating life test robustness of Schottky gate and ohmic gate GaN HEMT with comparable stress conditions](#)

Fawad Rauf¹, Muhammad Farhan Tayyab², Samir Mouhoubi², Marcelo Heldwein³, Gilberto Curatola²

¹TUM and HUAWEI, Germany, ²HUAWEI, Germany, ³TUM, Germany

[Study on intermittent fault mechanism of high-density integrated circuits under temperature shock](#)

Wenxiang Yang, Yong Zhang, Kehong Lv, Qiang Guo, Kai Shen, Jing Qiu

National University of Defense Technology, China

[Creep tester for quality assessment of solder joints using normal and thermal stress](#)

Jae-Seong Jeong, Young-Ki Ahn

Korea Electronics Technology Institute (KETI), South Korea

[Heat-resistant durability of AMB substrates for SiC power devices: AlN and Si₃N₄, which one is thermally strong?](#)

Yun-Chan Kim¹, Dong-Yurl Yu¹, Shin-il Kim¹, Yong-Mo Kim², Dongjin Byun³, Junghwan Bang¹, Dongjin Kim¹

¹Korea Institute of Industrial Technology (KITECH), South Korea, ²Korea Instrument Co., Ltd., South Korea, ³Korea University, South Korea

[Online Junction Temperature Monitoring of SiC MOSFET Based On The Maximum Drain Current Change Rate During The Process of Opening](#)

Hong Li¹, Yixiang Zhao¹, Xiaofei Hu¹, Qinghao Zhang²

¹Beijing Jiaotong University, China, ²Tsinghua University, China,

[Efficient Long-term Reliability Assessment of Planar InGaAs/InP Avalanche Photodiodes using Accelerated Step-Stress Test](#)

Yunseok Han¹, Sunho Kim², Ilgu Yun¹

¹Yonsei University, South Korea, ²Wooriro Co., South Korea

[Active Gate Driver for Current Overshoot Suppression of SiC+Si Hybrid Switches with Dynamic gate Current Regulation](#)

Ping Liu¹, Yongjie Liu¹, Qi Cao¹, Biao Xiao¹, Chunming Tu¹, Bin Yu^{2,3}

¹Hunan University, Changsha, China, ²Nanjing University of Information Science and Technology, China, ³Zhejiang University, Hangzhou, China

[Optimized Semi-Physical EKV Model for Simulation of SiC MOSFETs](#)

Benewende Diane Rainatou Bonkougou¹, Romain Gwoziecki¹, Gaetan Perez¹, Leo Sterna¹, Zoubir Khatir²

¹Univ. Grenoble Alpes, France, ²Univ. Gustave Eiffel, France

[A study of UIS ruggedness of mismatched paralleled SiC MOSFETs](#)

Ciro Scognamiglio¹, Antonio Pio Catalano¹, Lorenzo Codecasa², Alberto Castellazzi³, Vincenzo D'Alessandro¹

¹University of Naples Federico II, Italy, ²Politecnico di Milano, Italy, ³Kyoto University of Advanced Science, Japan

[The Use of Filtered High-Energy X-rays and ⁶⁰Co for TID Testing of a 32-Bit 28nm FDSOI DSP](#)

Alejandro Urena-Acuna¹, Julien Favrichon², Aurelien Ballier², Pierre-Alexis Robin², Vincent Gironés², Tadeo Maraine², Frederic Saigné², Jerome Boch²

¹Université de Toulouse, France, ²Univ. Montpellier, France

[Comprehensive LED Reliability Assessment through Integrated Real-Time Visualization, Electrical, and Optical Analysis](#)

Hui Teng Tan¹, Wardhana A. Sasangka¹, Yu Gao¹, Kenneth Eng Kian Lee¹, Carl V. Thompson², Chee Lip Gan³

¹Singapore-MIT Alliance for Research and Technology, Singapore, Singapore, ²Massachusetts Institute of Technology, USA, United States, ³Nanyang Technological University, Singapore, Singapore

[Machine learning classification for failure analysis of smart spark plugs](#)

Minh Long Hoang¹, Simone Daniele², Nicola Delmonte¹, Massimo Dal Re², Paolo Cova¹, Danilo Santoro¹

¹University of Parma, Italy, ²Federal-Mogul Italy s.r.l, Carpi, Italy

[Issues of electronic devices in hostile environment](#)

Valeria Trabattoni¹, Alessandro Andreani¹, Massimo Lazzaroni¹, Andrea Riminucci¹, Danilo Santoro², Andrea Zani³

¹Università degli Studi di Milano, Italy, ²University of Parma, Italy, ³INFN Sezione di Milano, Italy

[Methodology to estimate the impact of Single Event Transients in Logic](#)

Saumya Joshi, Rosina Menditto, Karsten Ermisch, Guenther Schindler, Joerg Berthold, Toni Huber, Steffen Rost¹, Katja Waschneck, Wolfgang Gustin, Georg Georgakos

Infineon Technologies, Germany

14:00 Workshop: Reliability of WBG Power Conversion

CHAIRS: *Fabio Coccetti¹, Thomas Harder²*

¹IRT Saint Exupéry, Toulouse, France, ²ECPE, Nurnberg, Germany

14:20 Session A-2: Reliability and Lifetime predictions focused on power electronics

CHAIR: *Edgar Olthof*

NXP Semiconductors, Netherlands

14:20 [Lifetime prediction for power modules in wind-energy converters based on temperature variations in a large area substrate solder connection](#)

Nils Zöllner¹, Oliver Schilling¹, David Übelacker¹, Hans-Günter Eckel², Tobias Heise²,

¹Infineon Technologies AG, Germany, ²University of Rostock, Germany

14:40 [On the Validity of Rainflow Counting-Based Lifetime Assessment for Power Electronics Assembly](#)

Dawei Zhao, Sebastian Letz, Jürgen Leib, Bernd Eckardt

Fraunhofer-Institute for Integrated Systems and Device Technology, Germany

15:00 [Reliability Prediction of Electronic Components based on Physical of Failure with Manufacturing Parameters Fluctuations](#)

Zijian Guo, Hao Chen, Yifan Hu, Xuerong Ye

Harbin Institute of Technology, Harbin, China

15:20 [Reliability prediction of multi-level power supply system based on failure precursor parameters](#)

Weiming Liu¹, Cen Chen¹, Wei Zheng², Mingtao Feng², Xuerong Ye¹, Guofu Zhai¹

¹Harbin Institute of Technology, Harbin, China, ²Beijing Aerospace Automatic Control Research Institute, China

15:40 [A New Methodology of Modeling Conducted Emission Behavioural in System-in-Packages \(SiP\)](#)

Yifei Zheng¹, Jianfei Wu¹, Yanfang Lu², Yang Li², Hongli Zhang², Peiguo Liu¹

¹National University of Defense Technology, China, ²Tianjin Institute of Advanced Technology, China

14:20 Session F3: Power devices reliability: power electronic systems

CHAIR: *Andrea Toscani*

University of Parma, Italy

14:20 [Series AC Arc Fault Diagnosis Method Based on Spectrogram and Deep Residual Network](#)

Wenxin Dai, Xue Zhou, Zhigang Sun, Guofu Zhai

Harbin Institute of Technology, Harbin, China

14:40 [Condition Monitoring of a DC-Link Capacitor in an Inverter with a front-end diode rectifier under Imbalanced Three-phase Supply Voltage](#)

Takuma Yamasoto, Kazunori Hasegawa

Kyushu Institute of Technology, Japan

15:00 [Analysis and experimental verification of current sharing among parallel-connected dc-link capacitors in a fast-switching converter](#)

Kazunori Hasegawa, Sakurako Nasu

Kyushu Institute of Technology, Japan

15:20 [Conducted EMI Assessment of Aging Power Si-MOSFET in 3 phase inverter](#)

Mohamed Tlig, Bessem Zitouna, Mahmoud Hammouda, Jaleddine Ben Hadj Slama

University of Sousse, Tunisia

15:40 [High AC load current testing method for power capacitors](#)

Fabian Dresel, Jürgen Leib, Lukas Blamberger, Bernd Eckardt, Martin März

Fraunhofer IISB, Germany

16:20 Session D: Reliability of microwave devices and circuits

CHAIR: *Michael Dammann*

Fraunhofer, Germany

16:20 [Reliability and Failure Analysis of AlGaIn/GaN HEMT with NiPtAu and PtAu Gate](#)

Michael Dammann¹, Peter Brückner¹, Rachid Driad¹, S. Krause¹, S.A. Albahrani¹, B. Weber¹, M. Baeumlere¹, H. Konstanzer¹, M. Mikullaa¹, M. Simon-Najasekb², S. Hübnerb², A. Graffb²

¹Fraunhofer Institute for Applied Solid State Physics, Freiburg, Germany, ²Fraunhofer Institute for Microstructure of Materials and System, Halle, Germany

- 16:40 [Study of Trapping Mechanisms Affecting AlGaIn/GaN HEMTs adopting AlGaIn Back- Barriers with Different Aluminum Concentrations](#)
Andrea Carlotto, Fabiana Rampazzo, Marco Saro, Francesco De Pieri, Manuel Fregolent, Carlo De Santi, Gaudenzio Meneghesso, Matteo Meneghini, Enrico Zanoni
 University of Padova, Italy
- 17:00 [Nonlinear modelling of AlN/GaN HEMT accounting for Self-biasing effect during RF step stress: analysis and Hard-SOA](#)
Nasri Said¹, Damien Saugnon², Kathia Harrouche³, Farid Medjdoub³, Nathalie Labat⁴, Nathalie Malbert⁴, Jean Guy Tartarin²
¹IMS Bordeaux - LAAS Toulouse, France, ²LAAS Toulouse, France, ³IEMN Lille, France, ⁴IMS Bordeaux, France
- 17:20 [DC and RF aging test of AlGaIn/GaN HEMT technology on SiC substrate](#)
Thomas Pallaro¹, Tristan Dubois¹, Magali De Matos¹, Christophe Chang², Nathalie Labat¹, Benoit Lambert², Nathalie Malbert¹
¹University of Bordeaux, France, ²United Monolithic Semiconductors, France

16:20 Workshop: Automotive Electronic, Driving into the Future

CHAIRS: *Rene Rongen¹, Ulrich Abelein², Francesco Leali³*

¹NXP Semiconductors, Netherlands, ²Infineon Technologies AG, Germany, ³MUNER, Modena, Italy

Wednesday, September 25th

08:20 Session F2-1: GaN&SiC: reliability and testing methodologies (1)

CHAIR: *Matteo Meneghini*

University of Padova, Italy

08:20 (Invited) Advanced Methodology and Understanding of GaN Device Reliability

Manuel Stabentheiner

Infineon Technologies Austria AG, Austria

09:00 [Gate voltage modulation for power cycling tests of SiC MOSFETs and its influence on temperature distribution](#)

Lukas R. Farnbacher¹, Jürgen Leib¹, Fabian Dresel¹, Andreas Schletz¹, Bernd Eckardt¹, Jörg Schulze²

¹Fraunhofer Institute IISB, Germany, ²Friedrich-Alexander-University of Erlangen-Nürnberg, Germany

09:20 [Test Methodology for Short-Circuit Assessment Applied to Power SiC MOSFETs](#)

Joao Oliveira¹, Jean-Michel Reynes¹, Hervé Morel², Pascal Frey¹, Olivier Perrotin³, Michel Piton⁴, Fabio Coccetti¹

¹IRT Saint Exupéry, France, ²INSA/Ampère, France, ³Alter⁻ Technology, France, ⁴Alstom, France

09:40 [A Screening Test of GaN-HEMTs for Improvement of Breakdown Voltage Uniformity](#)

Wataru Saito, Shin-Ichi Nishizawa

Kyushu University, Japan

10:00 [Dependence between the drain current saturation and short-circuit robustness of p- GaN HEMTs](#)

Mohamed Lemine Dedew¹, Stéphane Lefebvre¹, Tien Anh Nguyen¹, Thanh Long Le², Valeria Rustichelli³, Joao Oliveira³, Maroun Alam³, Fabio Coccetti³

¹SATIE, Cnam, CNRS, ENS Paris-Saclay, France, ²SAFRAN TECH, France, ³IRT Saint-Exupéry, France

09:00 Session BPA: Best papers ISTFA 2023 and IPFA 2024

CHAIRS: *Matteo Medda¹, Frank Altmann²*

¹ST Microelectronics, Italy, ²Fraunhofer, Germany

09:00 (ISTFA 2023 Best Paper) Finite Element Analysis (FEA) and Fractography: Complementary Methods in Understanding the Factors Resulting to Hairline Die Crack on Chip-On-Lead (COL) Devices

Melanie S. Cajita

Analog Devices, Inc., Philippines

09:20 (IPFA 2024 Best Paper) Reliability of Reconfigurable Field Effect Transistors: Early Analysis of Bias Temperature Instability

Giulio Galderisi

NaMLab GmbH, Germany

09:40 Session C: Progress in Failure Analysis: Defect detection and Analysis

CHAIRS: *Matteo Medda¹, Frank Altmann²*

¹ST Microelectronics, Italy, ²Fraunhofer, Germany

09:40 **(Invited) Physical Assurance for Advanced Packaging**

*Navid Asadi*¹

¹University of Florida, United States

10:40 [Localization enhancement in quantitative thermal lock-in analysis using spatial phase evaluation](#)

*Sebastian Brand*¹, *Michael Kögel*¹, *Christian Grosse*¹, *Frank Altmann*¹, *Hemachandar Tanukonda Devarajulu*², *Francisco M Benito*², *Deepak Goyal*², *Mario Pacheco*²

¹Fraunhofer IMWS, Germany, ²Intel Corporation Inc., United States

11:00 [Fast high-resolution X-ray nano tomography for failure analysis in advanced packaging](#)

Till Dreier, *Daniel Nilsson*, *Julius Hällstedt*

Excillum AB, Sweden

11:20 [Failure Analysis of Gold-plated Fuzz Button Contacts in Elevated Temperature](#)

*Lei Zhang*¹, *Shujuan Wang*², *Xueyong Chen*³, *Jianshe Guo*³, *Le Xu*², *Sanqiang Ling*³, *Xiaojuan Zhang*³

¹Harbin Institute of Technology, China Aviation Optical-Electrical Technology Co., Ltd., China, ²Harbin Institute of Technology, China,

³China Aviation Optical-Electrical Technology Co., Ltd., China

11:40 [Improved 2D charge carrier quantification workflow for scanning spreading resistance microscopy](#)

*Thomas Adlmaier*¹, *Stefan Doering*¹, *Boris Binder*¹, *Daniel K. Simon*¹, *Lukas M. Eng*², *Thomas Mikolajick*³

¹Infineon Technologies Dresden GmbH, Germany, ²Institute of Applied Physics, University of Technology Dresden, Germany, ³University of Technology Dresden, Germany

10:40 Session F2-2: GaN&SiC: reliability and testing methodologies (2)

CHAIR: *Matteo Meneghini*

University of Padova, Italy

10:40 [Analyzing the role of hole injection on the short circuit performance of p-GaN gate power HEMTs](#)

*Dominik Wieland*¹, *Boris Butej*², *Manuel Stabenheimer*¹, *Christian Koller*³, *Dionyz Pogany*⁴, *Clemens Ostermaier*³

¹TU Vienna, Infineon Technologies Austria AG, ²TU Vienna, KAI, Austria, ³Infineon Technologies Austria AG, ⁴TU Vienna, Austria

11:00 [Advanced Power Cycling Test Strategies on Discrete SiC MOSFETs in Different Operating Modes and the Impact on Life-time](#)

Lukas Hein, *Patrick Heimler*, *Tobias Lentzsch*, *Josef Lutz*, *Thomas Basler*

Chemnitz University of Technology, Germany

11:20 [Gate lifetime investigation at low temperature for p-GaN HEMT](#)

*Maroun Alam*¹, *Valeria Rustichelli*¹, *Moustafa Zerarka*¹, *Christophe Banc*², *Jean-Francois Pieprzyk*³, *Olivier Perrotin*⁴, *Romain Ceccarelli*⁴, *David Tremouilles*⁵, *Mohamed Matmat*¹, *Fabio Coccetti*¹

¹IRT Saint Exupéry, Toulouse, France, ²Safran Electronics & Defense, France, ³STMicroelectronics, Toulouse, France,

⁴Alter Technology, Toulouse, France, ⁵LAAS-CNRS, Université de Toulouse, CNRS, Toulouse, France

11:40 [Reliability of Discrete SiC MOSFETs under Temperature-Shock and Power Cycling Tests](#)

Patrick Heimler, *Sandro Richter*, *Josef Lutz*, *Thomas Basler*

University of Chemnitz, Germany

12:00-14:00 Poster Session 2

CHAIR: *Giovanna Mura*

University of Cagliari, Italy

[Spacecraft Sensor Reliability Improvement Based On Temporal Digital Twin Model](#)

Yingqi Wang, *Yuchen Song*, *Runze Yu*, *Shengwei Meng*, *Yu Peng*, *Datong Liu*

Harbin Institute of Technology, China

[A Floquet Theory-Based Stability Analysis Method for PV-Storage Independent DC Microgrid](#)

Hong Li, *Kuang Zhang*, *Jinchang Pan*, *Mingbo Wei*, *Yuanye Lu*

School of Electrical Engineering, Beijing Jiaotong University, Beijing, China

[Machine learning-based surrogate models for finned heatsink optimization](#)

Ziheng Wang, *Yi Zhang*, *Huai Wang*

Aalborg University, Denmark

[Electronics authentication using electrical measurements and machine learning](#)

*Simone Carta*¹, *Alessandro Urru*², *Michela Musa*², *Pietro Andronico*², *Giovanna Mura*¹

¹University of Cagliari, Italy, ²Nurjana Technologies srl, Italy

[Charging effects in alumina layers deposited with different precursors for microelectronic applications](#)

Vladimir Kolkovskiy, *Ronald Stübner*

Fraunhofer IPMS, Germany

[Enhancing AC Degradation Modeling by Considering the Degradation Profile in SiON pMOSFETs](#)

Yujin Kim, *Yeohyeok Yun*

School of Electrical, Electronics and Communication Engineering, KOREATECH, South Korea

[The effects of NBT stressing on later operation of power VDMOS transistors under normal conditions](#)

Sandra Veljković¹, Nikola Mitrović¹, Vojkan Davidović¹, Alben Paskaleva², Dencho Spassov², Igor Jovanović¹, Emilija Živanović¹, Goran Ristić¹, Danijel Danković¹

¹University of Nis, Serbia, ²Bulgarian Academy of Sciences, Sofia, Bulgaria

[Sorption getter characterization under wafer-level packaging \(WLP\) conditions](#)

Hélène Duchemin, David Bouchu

Univ. Grenoble Alpes, France

[Fast Reverse Engineering of Chips using Lasers, Focused Ion Beams, and Confocal and Scanning](#)

[Electron Microscopy](#)

Matthew Mascalco, Hongbin Choi, Adrian Phoulady, Alexander Blagojevic, Toni Moore, Mohammad Taghi Mohammadi Anaei, Parisa Mahyari, Nicholas May, Sina Shahbazmohamadi, Pouya Tavousi

UConn, United States

[Solid failure analysis flow for the detection of the leakage current in MEMS gyroscope resonant system](#)

Domenico De Rosa

STMicroelectronics, Italy

[GaN defect detection and analysis using electrical probing, EBAC, EBIC and EBIRCH](#)

Andreas Rummel¹, Andrew Smith¹, Greg Johnson², Heiko Stegmann³

¹Kleindiek Nanotechnik GmbH, Germany, ²ZEISS Research Microscopy Solutions, United States, ³Carl Zeiss Microscopy GmbH, Germany

[Failure investigation on an embedded Schottky Barrier Diode due to an inhomogeneous silicide formation](#)

Francis Nikolai Lupena¹, Timo Mohamed El Khawaga

Renesas Design Germany GmbH, Germany

[Power devices Failure Analysis Use Cases Using High voltage OBIRCh and EMMI workflows](#)

Elisa Vitanza¹, Chiara Realmuto¹, Antoine Reverdy², Paolo Dalla Ricca³

¹ST Microelectronics Catania, Italy, ²Sector technologies, France, ³ThermoFisher Scientific, United States

[A Submodule Capacitor Degradation Balancing Control with Capacitor Parameter Monitoring of a Modular Multilevel Converter for a Battery Energy Storage System](#)

Takumi Yasuda¹, Kazunori Hasegawa², Jun-Ichi Itoh³

¹Mitsubishi Electric, Japan, ²Kyushu Institute of Technology, Japan, ³Nagaoka University of Technology, Japan

[Assembly reliability of ceramic small outline packaged devices](#)

Wenyan Wang

China Academy of Space Technology, China

[FEM-based development of novel 3D-printable plastic direct coolers for power semiconductor modules](#)

Nicola Delmonte, Davide Spaggiari, Corrado Sciancalepore, Roberto Menozzi, Paolo Cova

University of Parma, Italy

[System in package: Advanced FA Techniques to Minimize Analysis Time and Cost](#)

Katalin Szász, Denise Luca

Renesas Electronics, Germany

[Evaluation with FEM Analysis of peak case non-rupture current for power devices working at very high current](#)

Davide Spaggiari¹, Paolo Cova¹, Federico Portesine², Marco Aschero², Nicola Delmonte¹

¹University of Parma, Italy, ²Poseico S.p.A., Genova, Italy

[Microstructure-based fatigue analysis of SiC power module with sintered silver die attach](#)

Zhihao Guo¹, Shuibao Liang¹, Saran Ramachandran², Han Jiang³, Yaohua Xu³, Zhihong Zhong¹

¹Hefei University of Technology, China, ²University of Strathclyde, UK, ³Anhui University, China

[Understanding improved pitting corrosion resistance under high temperature application leading to a newly developed palladium coated copper wire](#)

Noritoshi Araki¹, Motoki Eto¹, Teruo Haibara¹, Takashi Yamada¹, Robert Klengel², Sandy Klengel²

¹Nippon Micrometal Corporation NMC, Japan

²Fraunhofer IMWS, Germany

[Impact of Device Encapsulation on the Time-Dependent Dielectric Breakdown in Polymeric Dielectrics for Galvanic Isolation](#)

Matteo Greatti¹, Jurij Lorenzo Mazzola¹, Lorenzo Cantù¹, Christian Monzio Compagnoni¹, Alessandro Spinelli¹, Dario Paci², Fabrizio Speroni², Michele Lauria², Vincenzo Marano², Gerardo Malavena¹

¹Politecnico di Milano, Italy, ²STMicroelectronics, Italy

[Solder Stop as a Reliable Insulation Layer on Printed Circuit Boards – Different Layouts and Materials under Humidity and High Voltage](#)

Michael Vogt¹, Alexander Brunko¹, Markus Meier², Helmut Schweigart², Lothar Henneken³, Michael Schleicher⁴, Detlev Schucht⁵, Nando Kaminski¹

¹University of Bremen, Germany, ²Zestron Europe, Dr. O.K. Wack Chemie GmbH, Germany, ³Robert Bosch GmbH, Germany, ⁴Semikron-Danfoss, Semikron Elektronik GmbH & Co. KG, Germany, ⁵Lackwerke Peters GmbH & Co. KG, Germany

[The Effect of Trench Depth on Single-Event Burnout Hardening of Split-Gate-Trench MOSFET](#)

Shuo Liu, Fengkai Liu, Zhongli Liu, Lei Wu, Jianqun Yang, Xingji Li

Harbin Institute of Technology, China

[Thermal Impedance and Local Thermal Runaway during Surge Events in Power Rectifiers](#)

Ole Bergmann¹, Tim Böttcher², Hoan Vu², Hoc Khiem Trieu³

¹Delft University of Technology, Netherlands, ²Nexperia Germany GmbH, Germany, ³Hamburg University of Technology, Germany

[Separate Investigation of Performance Degradation for the Si and GaN parts in Cascode GaN devices under Repetitive Short Circuits](#)

Zhebie Lu, Francesco Iannuzzo

Aalborg University, Denmark

[Investigation of Trade-off between Switching Loss and Gate Overshoot in SiC MOSFETs by Driving Waveform Modification](#)

Bang-Ren Chen¹, Cheng Sung¹, Yu-Sheng Hsiao¹, Wei-Chen Yu Yu², Yi-Jun Dong¹, Wei-Cheng Lin¹, Surya Elangovan², Yi-Kai Hsiao², Hao-Chung Kuo², Chang-Ching Tu³, Tian-Li Wu¹

¹National Yang Ming Chiao Tung University, Taiwan, ²Hon Hai Research Institute, Taiwan, ³National Central University, Taiwan

[Power Cycling Results of Cascode GaN Devices – Separate Analysis of Performance Degradation for Si/GaN parts and Lifetime Model](#)

Zhebie Lu, Francesco Iannuzzo

Aalborg University, Denmark

[Numerical simulation of current uniformity in Ga₂O₃ planar diodes and its effect on temperature field and device reliability](#)

Lorenzo Perini, Payam Rajabi Kalvani, Antonella Parisini, Roberto Fornari, Giovanna Sozzi

University of Parma, Italy

[Aging Effects on Short-Circuit Peak Current Through Gate-oxide Degradation in SiC MOSFET](#)

Farzad Hosseinabadi, Sajib Chakraborty, Omar Hegazy

Vrije Universiteit Brussel, Belgium

[Hail damage investigation in heterojunction silicon photovoltaic modules: a real word case study](#)

Marco Nicoletto¹, Davide Panizzon¹, Alessandro Caria¹, Nicola Trivellin¹, Carlo De Santi², Matteo Buffolo¹, Gaudenzio Meneghesso¹, Enrico Zanoni¹, Matteo Meneghini¹

¹University of Padova, Italy, ²University of Padova & National Interuniversity Consortium for Nanoelectronics, Italy

[A Geometry-Scalable Electrothermal Compact Circuit Model of SiC MPS Diodes Accounting for the Snapback Mechanism: Application to Current Surge Events](#)

Alessandro Borghese, Vincenzo Terracciano, Marco Boccarossa, Andrea Irace, Vincenzo D'Alessandro

University of Naples Federico II, Italy

[Long-term \(8000 h\) reliability and failures of high- power LEDs for outdoor lighting stressed at high ambient temperatures](#)

Alessandro Caria¹, Riccardo Fraccaroli¹, Giulia Pierobon¹, Thomas Castellaro¹, Ambrogio Huang¹, Julien Magnien², Joerdis Rosc², Gyula Lipák³, Gusztáv Hantos³, János Hegedüs³, Carlo De Santi¹, Matteo Buffolo¹, Nicola Trivellin¹, Enrico Zanoni¹, András Poppe³, Gaudenzio Meneghesso¹, Matteo Meneghini¹

¹University of Padova, Italy, ²Materials Center Leoben Forschung GmbH, Austria, ³Budapest University of Technology and Economics, Hungary

[Selective Hardening of RISC-V Soft-Processors for Space Applications](#)

Giorgio Cora, Corrado De Sio, Sarah Azimi, Luca Sterpone

Politecnico di Torino, Italy

[Impact of Constant and Pulsed Active Balancing Current Patterns on the Aging of Lithium-ion Batteries](#)

Muhammad Aitezaz Hussain, Alessandro Soldati, Giovanna Sozzi

¹University of Parma, Italy

[Characterization and Analysis of Single-Event Effects in 16 nm FinFET FPGAs Based on On-Orbit Data](#)

Zhi Chao Wei^{1,2}, Ran Zheng², Yi Sun¹, Hongwei Zhang¹, Bo Mei¹, Yinghui Liu¹

¹China Academy of Space Technology, China, ²Northwestern Polytechnical University

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Tsuriel Avraham, Joseph Bernstein

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Alessandro Sitta, Giuseppe Mauromicale, Michele Fiore, Michele Calabretta

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[Mechanical Characterization of Silicon Carbide- Coated Carbon Nanotube Composites via High-Temperature Compressive Testing for Hyper- interconnect Applications](#)

Leiming Du¹, Gerald Schaffar², Jiarui Mo¹, Verena Maier-Kiener², Daniel Kiener², Guoqi Zhang¹

¹Delft University of Technology, Netherlands, ²Montanuniversität Leoben, Austria

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Tomoyuki Mannen

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[Thermal Performance Comparison of Wide Bandgap Power Modules by Simulation](#)

Guesuk Lee, Jemin Kim, Byongjin Ma

Korea Electronics Technology Institute, South Korea

[Peak detection for current balancing of parallel- connected SiC power devices using PCB sensors](#)

Ravi Nath Tripathi, Ichiro Omura

Kyushu Institute of Technology, Japan

[ESD Human Body Model step stress distributions of GaN HEMTs and the correlation with one level test results](#)

Roelof van der Berg¹, Edwin Jellema²

¹Ampleon, Netherlands, ²Eurofins | Maser, Netherlands

[Improving Large-Area Sintering Reliability of Power Module Systems Using Copper Paste/Film](#)

Ke Li¹, Xiaochun Lv^{1,2}, Jun You¹, Minghao Zhou¹, William Cai¹, Jianbo Xin¹, Jicun Lu², Yang Liu³

¹Harbin University of Science and Technology, China, ²Harbin Welding Institute Limited Company, Harbin, China, ³Zhuhai Fudan Innovation Research Institute, China

[Development of Life Prediction Model based on Physics-of-Failure for Negative Temperature Coefficient Thermistor](#)

Hyoungseuk Choi

Korea Institute of Ceramic Engineering and Technology, South Korea

[Synergistic Effect of Total Ionizing Dose and Electromagnetic Interference in SRAM using 22nm FDSOI technology](#)

Yinyin Shang¹, Chenhe Gao¹, Xing Zhao¹, Binhong Li¹, Jianzhong Li², Jianfei Wu³, Hongli Zhang³, Yang Li³, Jun Luo¹, Tianchun Ye¹

¹Korea Institute of Microelectronics of the Chinese Academy of Sciences, China, ²Guangdong Greater Bay Area Institute of Integrated Circuit and System, China, ³Tianjin Advanced Technology Institutes, China

14:00 Session F2-3: GaN&SiC: reliability and testing methodologies (3)

CHAIR: *Matteo Meneghini*

University of Padova, Italy

14:00 [The impact of mold compound on power cycling capability of SiC MOSFETs in double sided cooled modules](#)

Tobias Lentzsch, Josef Lutz, Thomas Basler

University of Chemnitz, Germany

14:20 [Toward understanding the impacts of dynamic Ron on the efficiency in GaN-based AC-DC flyback converter](#)

Chih-Yao Chang¹, Hsing-Hua Hsieh¹, Huang-Pin Hsu¹, Cheng-Tsung Ho¹, Tsung-Hsiu Wu¹, Han-Wei Chen¹, Ming-Chang Tsou¹, Chih-Wen Hsiung¹, Ming-Nan Chuang¹, Tian-Li Wu²

¹Leadtrend Technology Corporation, Taiwan, ²National Yang Ming Chiao Tung University, Taiwan

14:40 [OFF-state Breakdown and Threshold Voltage Stability of Vertical GaN-on-Si Trench MOSFETs](#)

Manuel Fregolent¹, Francesco Bergamin¹, Davide Favero¹, Carlo De Santi¹, Christian Huber², Gaudenzio Meneghesso¹, Enrico Zanoni¹, Matteo Meneghini¹

¹University of Padova & National Interuniversity Consortium for Nanoelectronics, Italy, ²Robert Bosch GmbH, Renningen, Germany

15:00 [Improved CV characterization technique for interface state evaluation in Si₃N₄/n-GaN MIS Capacitors](#)

Anton Marco Hofer¹, Christian Koller², Nicola Modolo², Dionyz Pogany³, Clemens Ostermaier²

¹TU Wien, Infineon Technologies Austria AG, Austria, ²Infineon Technologies Austria AG, Austria, ³TU Wien, Austria

14:00 Workshop: Hardware Security Meets Failure Analysis

CHAIRS: *Navid Asadi¹, Frank Altmann²*

¹University of Florida, United States, ²Fraunhofer, Germany

15:40 Session F2-4: GaN&SiC: discrete device stability and reliability

CHAIR: *Matteo Meneghini*

University of Padova, Italy

15:40 [Evidence for double degradation regime in off-state stressed 100 V GaN transistors: from dielectric failure to subthreshold current increase](#)

Riccardo Fraccaroli¹, Manuel Fregolent¹, Mirco Boito¹, Carlo De Santi¹, Eleonora Canato², Isabella Rossetto², Maria Eloisa Castagna³, Ferdinando Iucolano³, Cristina Miccoli³, Alfio Russo³, Giansalvo Pizzo⁴, Gaudenzio Meneghesso¹, Enrico Zanoni¹, Matteo Meneghini¹

¹University of Padova, Italy, ²STMicroelectronics, Agrate Brianza, Italy, ³STMicroelectronics, Catania, Italy, ⁴STMicroelectronics, Cornaredo, Italy

- 16:00 [Interface-related VTH Shift of SiC MOSFETs during Constant Current Stress extracted from Charge Pumping measurements](#)
Alberto Marcuzzi¹, Marina Avramenko², Carlo De Santi¹, Peter Moens², Gaudenzio Meneghesso¹, Enrico Zanoni¹, Matteo Meneghini¹
¹University of Padova, Italy, ²Onsemi, Belgium
- 16:20 [Threshold Voltage Hysteresis Investigation of SiC MOSFETs with Different Structures under Various Measurement Conditions](#)
Dong Xie, Patrick Heimler Roman Boldyrjew-Mast, Mohamed Alaluss, Sven Thiele, Josef Lutz, Thomas Basler
 University of Chemnitz, Germany
- 16:40 [Ultra-Fast recovery transients in GaN MIS-HEMT submitted to OFF State stress](#)
Alberto Cavaliere¹, Nicola Modolo², Carlo De Santi¹, Gaudenzio Meneghesso¹, Enrico Zanoni¹, Matteo Meneghini
¹University of Padova, Italy, ²Infineon Technologies, Villach, Austria

Thursday, September 26th

08:20 Session E-1: Reliability of packages for power devices and sensors

CHAIR: *Nicola Delmonte*

University of Parma, Italy

- 08:20 **(Invited)** Virtual prototyping in power electronics: the role of simulation in developing reliable products
[Mirko Bernardoni¹](#)
¹Infineon Technologies Austria, Automotive Product Development, Austria
- 09:00 [Numerical study of critical filler particle to chip interaction on an automotive Hall sensor](#)
Falk Naumann¹, Michél Simon-Najasek¹, Bernd Wiesenberger², Achim Lindner², Frank Altmann¹
¹Fraunhofer Institute IMWS, Germany, ²TDK-Micronas GmbH, Germany
- 09:20 [Risk of CuxO phase penetration between the Ag plating layer and Cu during high-temperature reliability testing of interfaces bonded to cold sintered Ag nano-porous sheets on direct Ag-plated Cu substrates](#)
Yehri Kim¹, Eunjin Jo¹, Byeong Kwon Ju², Yoongul Lee³, Jaeup Kim³, Kijoon Ahn³, Seungjun Noh⁴, Dongjin Kim¹
¹Korea Institute of Industrial Technology (KITECH), South Korea, ²Korea University, South Korea, ³SP semiconductor, South Korea, ⁴Hyundai Mobis, Co., Ltd., South Korea
- 09:40 [Evaluation and thermal ageing of power semiconductor die attachment based on porous film electrodeposition](#)
Goulven Janod¹, Lucas Chachay¹, Jonathan Schoenleber², Yvan Avenas¹, Didier Bouvard¹, Remi Daudin¹, Jean-Michel Missiaen¹, Marie-Pierre Gigandet², Jean-Yves Hihn¹, Rabih Khazaka³
¹Grenoble-INP/UGA, France, ²UTINAM, France, ³SAFRAN-Tech, France
- 10:00 [Enhancing Long-Term Thermal Reliability of Sintered Joints through the Use of Silver-Coated Copper Particles](#)
Dajung Kim¹, Mi So Won¹, Hyunseung Yang¹, Chulmin Oh¹
¹Korea Electronics Technology Institute (KETI), South Korea

08:20 Session G: Photonics reliability

CHAIRS: *Matteo Buffolo¹, Yannick Deshayes²*

¹University of Padova, Italy, ²IMS Laboratory, France

- 08:20 **(Invited)** LED Reliability for Lighting Applications and Beyond
[Grigory Onushkin](#)
 Signify Research, Eindhoven, Netherlands
- 09:00 [Changes in the extraction and collection efficiency of GaN-based MQW solar cells under optical step-stress](#)
Marco Nicoletto, Alessandro Caria, Nicola Roccatò, Carlo De Santi, Matteo Buffolo, Gaudenzio Meneghesso, Enrico Zanoni, Matteo Meneghini
 University of Padova, Italy
- 09:20 [Evidence for Optically-Induced Degradation in CIGS Solar Cells](#)
Claudia Casu¹, Matteo Buffolo¹, Alessandro Caria¹, Carlo De Santi², Nicola Trivellini¹, Stefano Rampino³, Matteo Bronzoni³, Massimo Mazzer³, Gaudenzio Meneghesso¹, Enrico Zanoni², Matteo Meneghini¹
¹University of Padova, Italy, ²University of Padova & National Interuniversity Consortium for Nanoelectronics, Italy, ³CNR-IMEM Parma, Italy
- 09:40 [About the influence of temperature operation and packaging stress on the threshold for catastrophic optical damage in laser diodes](#)
Jorge Souto, José Luis Pura, Julian Anaya, Juan Jimenez
 University of Valladolid, Spain
- 10:00 [Degradation Modeling of InGaAs/InP Avalanche Photodiodes using Calibrated Technology Computer-aided Design](#)
Heewon Bang¹, Yunseok Han¹, Sunho Kim², Ilgu Yun¹
¹Yonsei University, South Korea, ²Wooriro Co., South Korea

10:40 Session E-2: Bond wire reliability

CHAIRS: *Olaf Wittler*¹, *René Rongen*²

¹Fraunhofer, Germany, ²NXP Semiconductors, Netherlands

10:40 [Wire bonding failure characterization of an IGBT based power module through impedance analysis](#)

*Paul-Etienne Vidal*¹, *Stéphane Baffreau*¹, *Guillaume Viné*¹, *Anusha Gopishetti*², *Than-Le Long*³

¹Université de Technologie de Tarbes, Toulouse University, France, ²Deep Concept, France, ³Safran, France

11:00 [Degradation mode analysis of Cu bond wires on Cu plated SiC power semiconductors stressed by active power cycling](#)

*Rasched Sankari*¹, *Ulrich Keßler*², *Martin Rittner*², *Borja Kilian*², *Youssef Maniar*², *Olaf Wittler*³, *Martin Schneider-Ramelow*⁴

¹Robert Bosch GmbH, Germany - Technical University Berlin, Germany, ²Robert Bosch GmbH, Germany, ³Fraunhofer-Institute, Germany,

⁴Technical University Berlin, Germany - Fraunhofer-Institute, Germany

11:20 [Thermal ageing monitoring in Cu-Al intermetallic joints through electrical resistance drift: comparative study of lifetime potential in pure and alloyed copper wires](#)

*Roberta Carluccio*¹, *Alberto Mancaleoni*¹, *Gabriele Losacco*¹, *Riccardo Villa*¹, *Andrea Serafini*¹, *Lucrezia Guarino*¹, *David Dellasega*²

¹STMicroelectronics, Italy, ²Politecnico di Milano, Italy

11:40 [Lifetime model for wire bond degradation in power semiconductors based on accelerated mechanical testing and power cycling](#)

*Bernhard Czerny*¹, *Golta Khatibi*², *He Du*³, *Francesco Iannuzzo*⁴

¹University of Applied Sciences Burgenland, Austria, ²TU Wien, Austria, ³Kyushu Institute of Technology, Japan, ⁴Aalborg University, Denmark

12:00 [Crack propagation in ultrasonic-bonded copper wires investigated by power cycling and accelerated mechanical fatigue interconnection test methods](#)

*Liz Karanja*¹, *Pierre-Yves Pichon*², *Marc Legros*¹

¹CEMES-CNRS, France, ²Mitsubishi Electric R&D Centre Europe, France

10:40 Session I: Extreme environments and Radiation

CHAIRS: *Marta Bagatin*¹, *Francesco Pintacuda*²

¹University of Padova, Italy, ²STMicroelectronics, Italy

10:40 (Invited) Non-volatile Memories for the Space Environment: Ionizing Radiation Effects

Simone Gerardin

University of Padova, Italy

11:20 [C-SMART: A preprocessor for neural network performance and reliability under radiation](#)

*Anuj Justus Rajappa*¹, *Philippe Reiter*¹, *Paolo Rech*², *Siegfried Mercelis*¹,

*Jeroen Famaey*¹

¹Imec- IDLab, Universiteit Antwerpen, Belgium, ²University of Trento, Italy

11:40 [The behavior of 350V GaN HEMTs during heavy ion irradiations](#)

*Francesco Velardi*¹, *Giovanni Canale Parola*¹, *Simone Palazzo*¹, *Emanuele Martano*¹, *Annunziata Sanseverino*¹, *Luca Silvestrin*², *Carmine Abbate*³, *Giovanni Busatto*¹

¹University of Cassino, Italy, ²University of Padova, Italy, ³DAC Engineering and Research srl, Italy

12:00 [Optimization of the drain-side configuration in ESD-protection SCR-LDMOS for high holding- voltage applications](#)

*Laura Zunarelli*¹, *Simone Rotorato*¹, *Elena Gnani*¹, *Susanna Reggiani*¹, *Raj Sankaralingam*², *Mariano Dissegna*², *Gianluca Boselli*²

¹University of Bologna, Italy, ²University Texas Instruments, United States

12:20 Closing Session

CHAIR: *Paolo Cova*

University of Parma, Italy

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EXHIBITORS





Issues of electronic devices in hostile environment

A. Andreani^a, M. Lazzaroni^{a,b}, A. Riminucci^a,
D. Santoro^{b,c}, V. Trabattoni^{a,b}, A. Zani^b

^a *Department of Physics, Università degli Studi di Milano, Milano, Italy*

^b *Sezione di Milano, INFN, Milano, Italy*

^c *Department of Engineering and Architecture, Università degli Studi di Parma, Parma, Italy*

Abstract

The operation of electronic devices in hostile environment has been investigated. Issues due to Extremely Low Temperature (i.e., Cryogenic temperature) and operation in cryogenics liquids (liquid argon, LAr, or liquid nitrogen, LN₂) are presented and discussed. Both passive and active electronics components have been considered and their troubles at cryogenics temperature have been presented.

1. Introduction

In the last few years, the interest in characterizing electronic devices operating in hostile environments has been growing due to the progress achieved in applied particle physics, involving the presence of cryogenic scintillators and cryogenic setups to optimize detection rates. Operation in cryogenic environment aims at improving the intrinsic efficiency of detectors used in astrophysics, particle physics and nuclear physics: in these conditions, it is possible to reduce signal-to-noise ratios (SNR), but usually one must minimize the mass of power electronics and front-end readout circuits, aiming at minimum power dissipation required.

A new challenge has been presented for modern liquid argon-based neutrino experiments (LAr-TPCs) which exploit photon detectors (PhotoMultiplier Tubes, PMTs, and Silicon PhotoMultipliers, SiPMs) immersed in liquid argon (LAr), acting as scintillating medium. This is the case for experiments like ICARUS, MicroBooNE, and more recently DUNE and its Prototypes at CERN. In these experiments, electronics must survive at 87 K, for extended periods of time (data-taking spans many years), and it must have a minimal power dissipation, as even a small amount of bubbling in the liquid can disrupt the operation of the detectors. Furthermore, recently R&D led to the idea of placing photon detectors on (very) high voltage surfaces (up to -300 kV, in DUNE), thus making it impossible to feed bias to the

devices, and extract signals, via standard copper cables. For this reason, power through optical fibers, implementing a Power over Fiber (PoF) technology at cryogenic temperatures, can be proposed and are investigated.

The low temperature, combined with the high voltage environment, requires an accurate preliminary study of the commercial electronic devices and their performances in such hostile set-up. Although some electronic components can operate at cryogenic temperature, every commercial technology must be tested and characterized beforehand, since the lack of suitable models to simulate the circuit behaviour makes the design very difficult, as performance estimated with commercial tools is unreliable and, in any case, limited to relatively high temperatures (i.e., 50 °C). Therefore, the behaviour of electronics components at cryogenic temperature is still open to investigation.

It is very important to underline that the focus should be pointed on the Dependability and not restricted to reliability (which is, obviously, the most important aspect). Dependability means RAMS: Reliability, Availability, Maintainability and, Safety. In high complexity experiments the Reliability is of paramount importance because maintenance can be operated only in well-defined periods, typically named shutdown period or shutdown time. In the case of LAr-based neutrino detectors, the condition is even more restrictive, as it will not be possible to intervene on the electronics during data taking. A failure

occurred during the operation (data taking) cannot be addressed, therefore component mortality and ageing issues must be addressed beforehand with intensive characterization campaigns and repeated thermal cycling.

Safety, not further developed in this paper, is also a very important aspect of the dependability.

The presence of radiation or magnetic fields, which also significantly affect electronics operations, are not of concern for most LAr-based neutrino experiments of the present generation, but dedicated studies should be performed, in view of next-generation programs.

In this manuscript, some considerations about the reliability of the devices (but also of the electronic systems) will be discussed taking into account operations at Extremely Low Temperature (i.e., Cryogenic temperature).

The paper is organized in the following manner. After some preliminary considerations in Section 2, Section 3 of the manuscript is devoted to passive electronic devices whereas in the following Section 4 active components have been taken into account. Conclusions are, finally, given in Section 5.

2. Some preliminary considerations

In the late 30 years, many studies were made to characterize the behaviour of electronic components in hostile environments. In particular, here we focus on the use of electronics at cryogenic temperature (below $-75\text{ }^{\circ}\text{C}$) for different applications, such as modern detectors in applied particle physics.

In the following, the discussion is confined to components characterization. However, it should be noted that issues arise also at interfaces, e.g. between components and Printed Circuit Boards (PCBs). This is particularly true for repeated temperature cycles: PCBs could undergo tiny deformations, leading to tension on the soldering, ruptures, unsteady contacts. These issues may arise both on the leads of passive components and on the pins of integrated circuits. The same issues may appear also on surface-mounted components.

3. Passive components

In this section, passive components such as resistors, inductors and capacitors were investigated and discussed.

3.1. Resistors

Resistors are passive two-terminal electrical components characterized by a resistance nominal value.

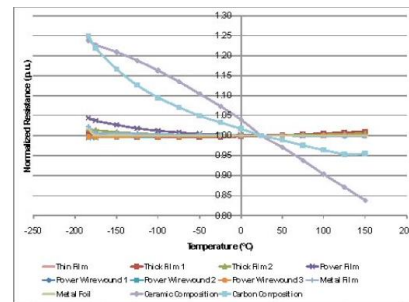


Fig. 1 Trend of resistance value, normalized to nominal value, as a function of temperature.

A primary categorization of resistors can be based on their assembly type. They can be either Pin Through Hole (PTH) or Surface Mount Device (SMD) resistors.

In literature, there are no studies exclusively dedicated to the behaviour of resistors at cryogenic temperatures. However, several papers that address this issue can be found for different applications. In general, resistor properties remain stable even at low temperatures (see Fig. 1). However, exceptions are observed for certain resistor types, specifically thick-film resistors, metal oxide resistors, and ceramic and carbon composition resistors. These particular devices exhibit a slight deviation in resistance values after undergoing a cooling cycle, rendering them less suitable for use in cryogenic conditions.

3.2. Capacitors

Capacitors are passive two-terminal electrical components enabling the accumulation of charges, making them valuable for energy storage within circuits. Capacitors are frequently employed as filters or for decoupling direct and alternating components of a signal, as they impede the passage of direct current. The capacitance value of a capacitor is influenced by the dielectric material used and its geometry. Similar to resistors, capacitors can also be categorized as SMD or PTH. Various types of capacitors, all Surface Mount Device, have been examined in the literature, in particular ceramic and polymer capacitors.

Capacitor characterization comes in different flavours: in some instances, measurements were conducted at well-defined temperatures, such as 300 K and 77 K, or at 300 K, 77 K, and 4K. In other cases, capacitance as a function of temperature was studied.

In all cases, measurements were performed at room temperature after cooling, to ensure survival after the cycle. The measurements were taken at various frequencies to analyse the behaviour of capacitance and current losses across different frequency ranges. Specifically, the frequencies investigated consistently

fell within the range of 50 Hz to 100 kHz.

These studies reveal that for certain capacitor types, including polymer capacitors (polypropylene, polyester, PPS, polycarbonate), NPO ceramic capacitors, and mica capacitors, the capacitance values remain relatively constant, with only small variations of 10% or less as detailed in the finale paper. Additionally, these capacitors exhibit low ohmic losses and low dissipation, which either remain constant or decrease as the temperature decreases.

In the only study carried out at temperatures below 77 K, polymer capacitors exhibited a decrease in capacitance values at 4 K, whereas the capacitance value for NPO capacitors remained approximately constant. On the other hand, various other ceramic capacitors display a stronger dependence on temperature, with variations exceeding 50% in capacitance values. Tantalum capacitors not only exhibit variations of 20% or more but also demonstrate a pronounced dependency on operating frequency.

Capacitor selection therefore is fundamental and must match the range of cryogenic temperatures and required frequency at which power electronics and read-out circuits must operate during the experiment.

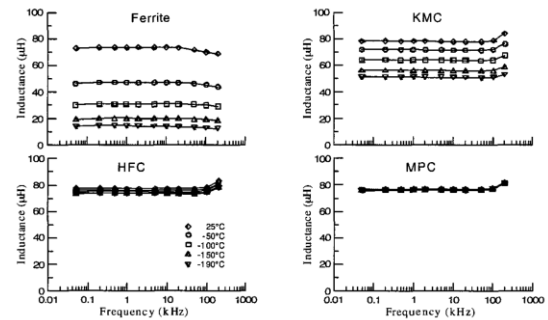
3.3. Inductors

Inductors are passive two-terminal devices characterized by a high inductance value.

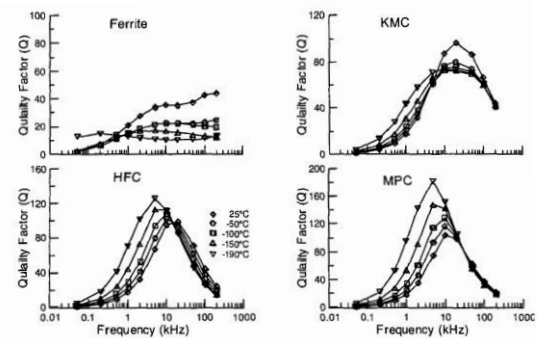
Inductors are often employed to store electrical energy through magnetic fields or as filters, given their high inductance that tends to obstruct the passage of signals at high frequencies. They are constructed as windings of conductive wires around ferromagnetic cores. The inductance value is contingent on the materials employed, the geometry and the number of turns in the winding around the core of the device itself.

Studies on inductors at cryogenic temperatures have primarily focused on investigating the structure of the magnetic core and the winding. A study conducted on copper wires discovered that as the temperature decreases, more windings are necessary to achieve the same inductance value. In contrast, other groups examined the windings' response while utilizing superconductors. Once again, tests are either carried out at fixed temperature values, or as a function of slowly varying temperature.

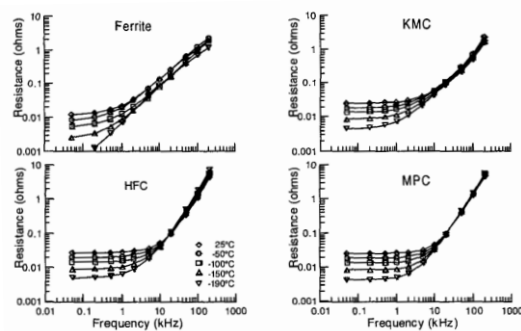
As a result, nanocrystalline materials stand out as the best choice for magnetic cores of inductors (see Fig. 3): these materials exhibit limited degradation in their characteristics at low temperatures compared to other materials, despite having the highest cost.



(a) Variation of inductance as a function of temperature and frequency.



(b) Variation of quality factor as a function of temperature and frequency.



(c) Variation of resistance as a function of temperature and frequency.

Fig. 2 Comparison of ferrite and powder cores.

On the other hand, the best compromise between performance and cost is achieved with ferrite cores.

4. Semiconductor devices

In general, research on semiconductors has revealed that they exhibit improved electronic, electrical, and thermal properties at lower temperatures, extending down to the temperature of liquid nitrogen. This improvement is attributed to increased carrier mobility and saturation rates, enabling higher

operating speeds. Lower temperatures also lead to significant enhancements in the thermal conductivity of device materials and substrates, simplifying thermal management and enhancing overall reliability. Additionally, at cryogenic temperatures, both conduction losses and switching losses of power devices decrease, leading to increased power conversion efficiency. A table summarising the behaviour of semiconductor devices at different temperatures will be added in the final paper.

4.1 Diodes

Diodes are non-linear passive components made from doped semiconductors, providing them with the capability to conduct current in only one direction. Operating with a threshold mechanism, diodes, to a first approximation, prevent current flow until the applied voltage at their ends surpasses a specific value. Once this threshold is exceeded, they can facilitate current flow without any restriction. This characteristic makes diodes ideal components for constructing rectifier circuits.

The study conducted on diodes examined how their characteristics, including junction voltage, breakdown voltage, and reverse current losses, change with temperature variations. Specifically, breakdown voltage and reverse current losses decrease with temperature, whereas junction voltage increases. All these observed phenomena can be attributed to the freezing effect of charges at low temperatures.

Germanium diodes exhibit favourable behaviour at cryogenic temperatures. A diode that enhanced its characteristics at low temperatures, specifically at 4 K has been developed. Studies were focused on Schottky diodes in GaAs. These diodes possess interesting characteristics such as a low threshold voltage, low resistance in the active region, and strong rectification performance. The study encompassed a temperature range from 20 K to 300 K.

4.2 Transistor

Transistors are three-pole electronic components, typically crafted from doped semiconductors. Their versatile structure, which can vary significantly based on construction methods, makes them capable of operating under different conditions, making them fundamental components for computational operations. Transistors play a crucial role in Resistor Transistor Logic (RTL) and are used for logic gates in digital electronics.

In particular, one study investigated MOS-FETs parameters between 300 and 77 K, focusing on: on-state resistance (R_{ON}), drain-source breakdown

voltages (V_{dsmax}), and initial turn-on voltages through their integrated reverse diodes (V_{diode}).

It is apparent that R_{ON} exhibits a minimum which occurs when the maximum electron mobility coincides with the minimum freezing effect of the charge carriers. As for V_{dsmax} and V_{diode} , they demonstrate linear correlations with temperature, particularly with directly and inversely proportional trends, respectively.

An investigation was conducted on R_{ON} at a fixed temperature (77K) while varying the drain current (I_D). In this case as well, a minimum value is observed at high currents, attributed to internal heating of the transistor resulting from current flow.

These performance findings give rise to two fundamental boundary conditions: the practical operating voltage must be within the reduced V_{dsmax} at cryogenic temperature, and the use of power diodes is generally not recommended at cryogenic temperature. Furthermore, despite the observed increase in on-state resistance at temperatures below 130 K, the study of the relationship between R_{ON} and I_D suggests that MOS-FET transistors can be effectively utilized at low temperatures while enhancing their performance, especially for high-current applications.

Antimony-based High Electron Mobility Transistors (HEMTs) were also examined in literature, comparing their properties at room temperature and at 77 K.

Additionally, dedicated studies on HEMTs in GaN and MOS-FETs in SiC have been conducted, investigating the characteristics of these devices under varying temperature conditions.

In the final paper, the performances of semiconductor components in cryogenic environments will be deeply discussed.

4.3 Systems

Among the various systems examined, there are oscillator, Pulse Width Modulated controllers and DC-DC converters and so on. Due to space constrain, these aspects will be discussed in the finale paper.

5. Conclusions

The operation of electronic devices in hostile environment has been discussed in this manuscript highlighting how low temperature influences the behaviour of electronic devices.

References

References will be added in the final paper.